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APPLICATION NO. FILING DATE		FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.		
10/809,033	03/25/2004	Takatomo Sasaki	o Sasaki 10873.1440US01			
53148 7	53148 7590 03/07/2006			EXAMINER		
HAMRE, SC	HUMANN, MUELLE	HECKENBERG J	HECKENBERG JR, DONALD H			
P.O. BOX 2903		ART UNIT	PAPER NUMBER			
MINNEAPOLIS, MN 55402			1722			
		DATE MAILED: 03/07/2006				

Please find below and/or attached an Office communication concerning this application or proceeding.

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		Applic	ation No.	Applicant(s)			
Office Action Summary		10/80	9,033	SASAKI ET AL.			
		Exami	ner	Art Unit			
		Donald	Heckenberg	1722			
The MAILIN Period for Reply	G DATE of this communicat	ion appears on	the cover sheet with the	correspondence ad	ddress		
WHICHEVER IS L - Extensions of time may after SIX (6) MONTHS (6) - If NO period for reply is Failure to reply within the Any reply received by the second	TATUTORY PERIOD FOR ONGER, FROM THE MAIL be available under the provisions of 37 from the mailing date of this communic specified above, the maximum statuto e set or extended period for reply will, he Office later than three months after the strent. See 37 CFR 1.704(b).	ING DATE OF CFR 1.136(a). In nation. Ty period will apply are by statute, cause the	THIS COMMUNICATION be event, however, may a reply be tind will expire SIX (6) MONTHS from application to become ABANDONE	N. mely filed the mailing date of this of (35 U.S.C. § 133).			
Status							
1) Responsive	to communication(s) filed o	n <u>23 Septemb</u>	<u>er 2005</u> .				
2a) This action is	☐ This action is FINAL . 2b) ☐ This action is non-final.						
3) Since this ap	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is						
closed in acc	cordance with the practice u	ınder <i>Ex parte</i>	Quayle, 1935 C.D. 11, 4	53 O.G. 213.			
Disposition of Claims	3						
4a) Of the ab 5) ☐ Claim(s) 6) ☒ Claim(s) <u>1-4</u> 7) ☐ Claim(s)		ithdrawn from					
Application Papers							
9) The specifica 10) The drawing(Applicant may Replacement	tion is objected to by the Exs) filed on <u>04 August 2004</u> not request that any objection drawing sheet(s) including the eclaration is objected to by	is/are: a)⊠ ac n to the drawing(correction is rec	s) be held in abeyance. Se quired if the drawing(s) is ob	e 37 CFR 1.85(a). ejected to. See 37 C	FR 1.121(d).		
Priority under 35 U.S.	.C. § 119						
12) Acknowledgn a) All b) S 1. Certifie 2. Certifie 3. Copies	nent is made of a claim for a Some * c) None of: ed copies of the priority doced copies of the priority doced copies of the priority doces of the certified copies of the diion from the International and detailed Office action for	cuments have to cuments have to ne priority docu Bureau (PCT f	peen received. Deen received in Applicat Dements have been receive Rule 17.2(a)).	ion No ed in this National	Stage		
	Cited (PTO-892) n's Patent Drawing Review (PTO- e Statement(s) (PTO-1449 or PTC		4) Interview Summary Paper No(s)/Mail Do 5) Notice of Informal F	ate	O-152)		
Paper No(s)/Mail Date		,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	6) Other:				

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- 1. Applicant's election of Group I (claims 1-46) in the reply filed on 23 September 2005 is acknowledged. Because Applicant did not distinctly and specifically point out the supposed errors in the restriction requirement, the election has been treated as an election without traverse. MPEP § 818.03(a).
- 2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 3. Claims 1-46 are rejected under 35 U.S.C. 102(b) as being anticipated by Hunter (U.S. Pat. No. 6,296,956).

Hunter discloses a method for forming single crystals of aluminum nitride. The method includes a step of heating a source material so as to sublimate or evaporate the material into an aeirform-gas substance (cl. 2, 11. 54-67). The aeriform substance is then crystallized to grow the single crystal under

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pressure (see example at cl. 12, l. 45 - cl. 13, l. 20). Hunter notes that using the method, growth rates of greater than 0.5 mm/hour (500 μ m/hour) are achieved (cl. 3, ll. 30-36).

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Hunter discloses that solid forms of aluminum or aluminum nitride powder may be used as an initial source material for the aeriform gas (cl. 2, ll. 54-57). Hunter also discloses the method may include the use of mixtures nitrogen, ammonia, and inert gases as carrier gases for the source material (cl. 2, l. 59 - cl. 3, l. 10; cl. 12, ll. 13-21). Hunter still further discloses impurities may be included in the gases so as to then be included in the crystal (cl. 12, ll. 1-15).

In various embodiments, Hunter notes that the aluminum source material is heated between 1000 °C to 2400 °C (cl. 10, ll. 61-64), and the pressure may be held at 1,000 torr (1.32 atm) during part of the crystal growth phase (cl. 13, ll. 1-5). Hunter also notes embodiments wherein films such as single crystal aluminum nitride or silicon carbide may be used as a seed-nucleus on which the single crystal in grown (cl. 12, ll. 36-42), with such a seed-nucleus having a diameter such as 2.25 inches (cl. 12, ll. 50-54).

4. Claims 1-5, 33, 34, 45, and 46 are rejected under 35 U.S.C. 102(e) as being anticipated by Schowalter (U.S. Pat. No. 6,770,135).

Schowalter discloses a method for producing large, single-crystals of aluminum nitride. In Schowlater's method, a source material of aluminum nitride is heated to evaporate or sublimate in order to form a aeriform substance (cl. 13, ll. 46-55). The aeriform substance is then crystallized under super-atmospheric pressure to grow the aluminum nitride single crystal (cl. 13, l. 55 - cl. 14, l. 27).

Schowalter further discloses the method to be conducted in an nitrogen gas containing atmosphere (see for example, cl. 13, ll. 40-46). Using the disclosed method, Schowalter notes growth rates of 0.9 mm/hr may be achieved (cl. 14, ll. 28-36).

- 5. The following reference cited but not relied upon is deemed pertinent to the instant application:
- Hunter (U.S. Pat. No. 6,086,672) discloses growth of bulk single crystals of aluminum nitride: silicon carbide alloys.
- 6. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Donald

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Heckenberg whose telephone number is (571) 272-1131. The examiner can normally be reached on Monday through Friday from 9:30 A.M. to 6:00 P.M.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Duane Smith, can be reached at (571) 272-1166. The official fax phone number for the organization where this application or proceeding is assigned is (571) 273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at (866) 217-9197 (toll-free).

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Donald Heckenberg Primary Examiner

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